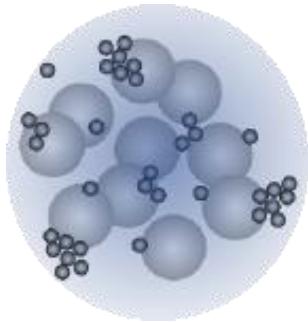


Direct numerical simulation for viscoelastic analysis of concentrated colloidal suspensions

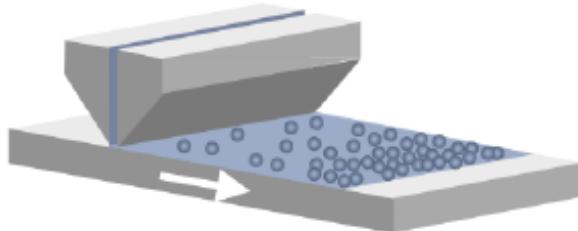
粒子系濃厚溶液の粘弾性特性の直接数値シミュレーション

- 辰巳 恵 (東大環安セ)
小池 修 (PIA)
- 山口 由岐夫 (PIA)
- 辻 佳子 (東大環安セ/東大院工)

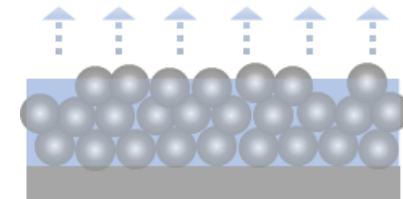
Material Fabrication from Colloidal Suspensions²



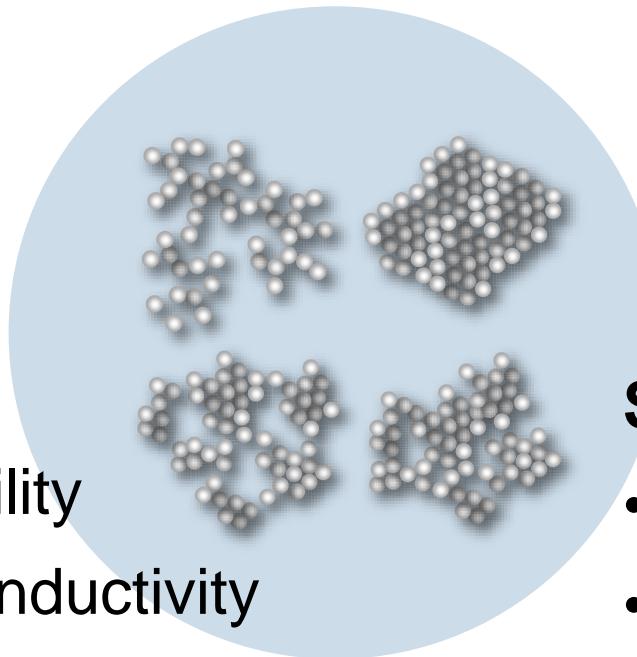
Dispersing



Coating



Drying



Functions

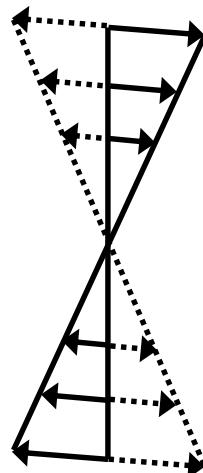
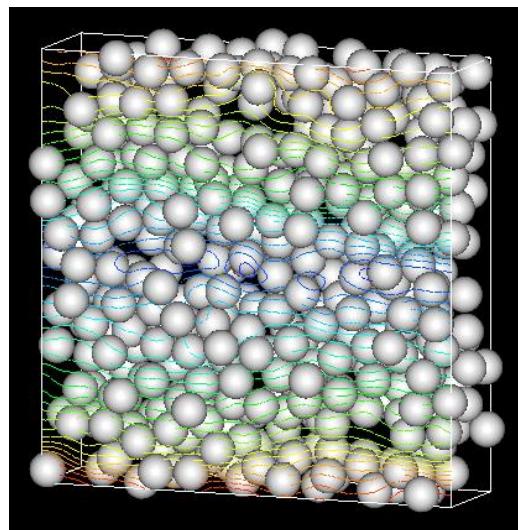
- Strength
- Permeability
- Electrical/Thermal conductivity
- Optical property

Structures

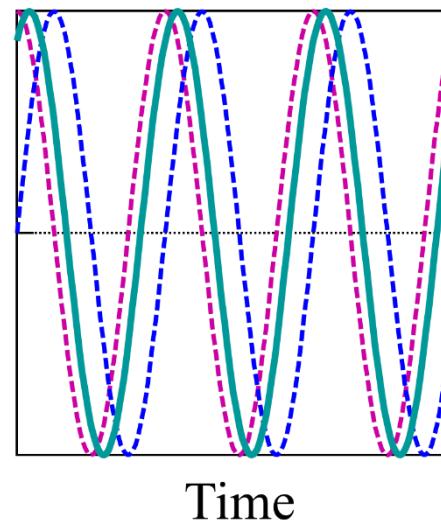
- Porosity
- Contact network

Objective

- ◆ Direct numerical simulation of viscoelastic behavior of concentrated colloidal suspensions
- ◆ Relation between dynamic modulus and the structure of particles



Oscillatory shear



Time

Shear strain/rate
 $\gamma(t) = \gamma_0 \sin \omega t$
 $\dot{\gamma}(t) = \gamma_0 \omega \cos \omega t$



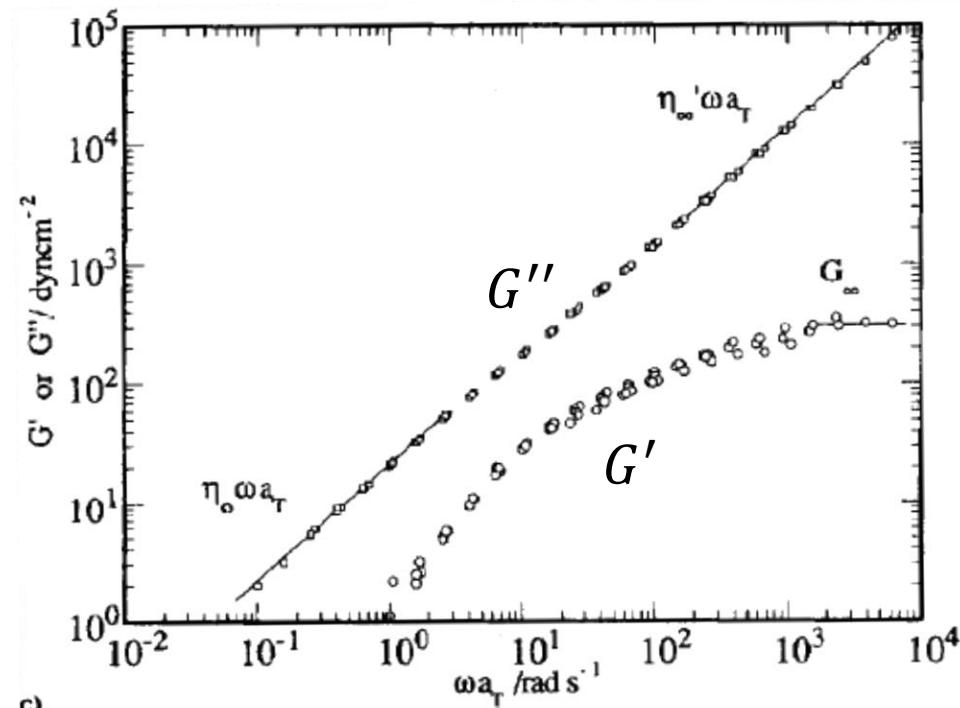
Stress
 $\sigma(t) = \sigma_0 \sin(\omega t + \delta)$



Dynamic modulus

$$G' = \frac{\sigma_0}{\gamma_0} \cos \delta \quad G'' = \frac{\sigma_0}{\gamma_0} \sin \delta$$

Dynamic modulus

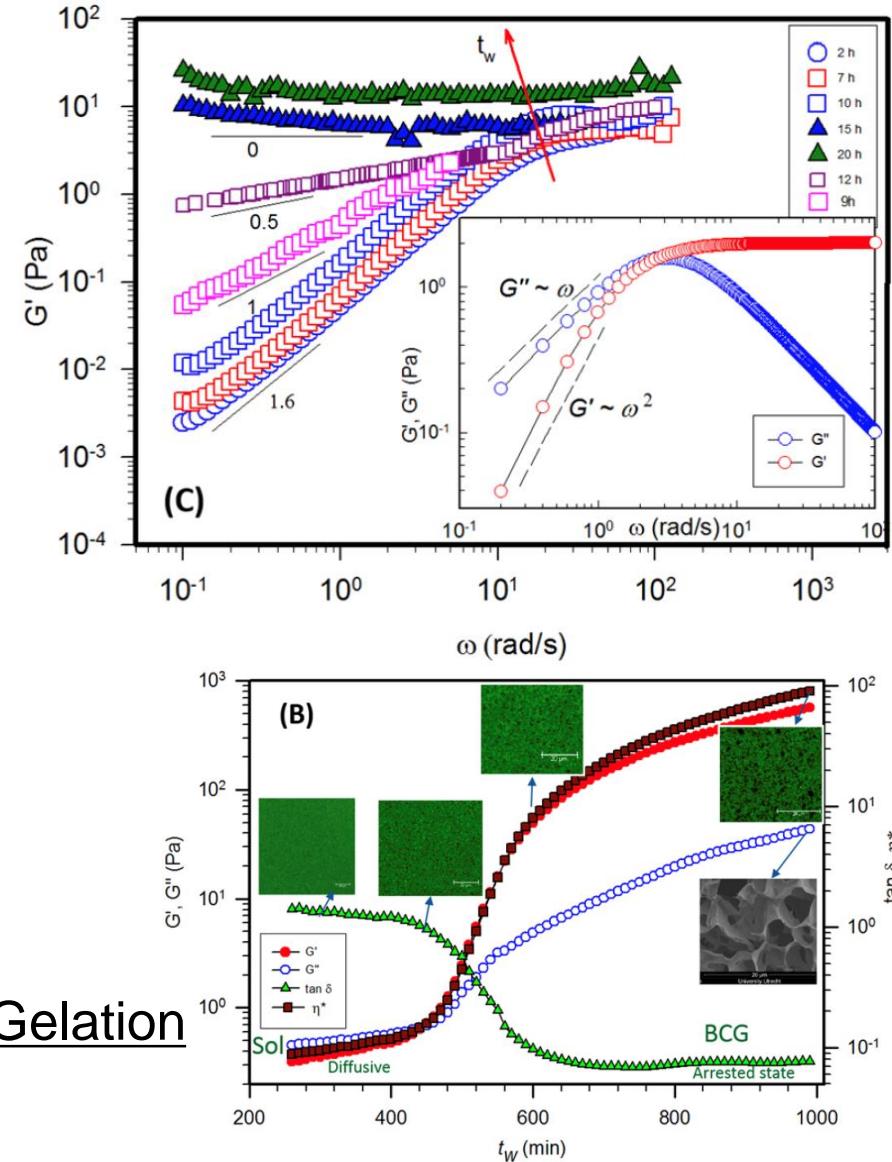


Well-dispersed system

Silica (60 nm, 37 vol%)
Ethylene glycol/Glycerol solvent

Shikata & Pearson, J. Rheol. (1994).

Pujala et al., Sci. Rep. (2018).



Equations

Particles

$$M \frac{dV}{dt} = \mathbf{F}^H + \mathbf{F}^{PP}$$

• Van der Waals force
• Contact force

$$I \frac{d\Omega}{dt} = \mathbf{N}^H + \mathbf{N}^{PP}$$

Hydrodynamic force

Fluid

$$\rho \left(\frac{\partial \mathbf{v}}{\partial t} + \mathbf{v} \cdot \nabla \mathbf{v} \right) = \nabla \cdot \boldsymbol{\sigma}_F + \Phi f_P$$

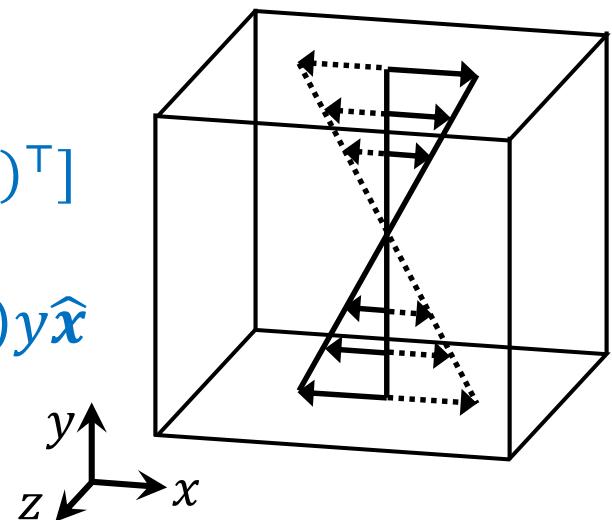
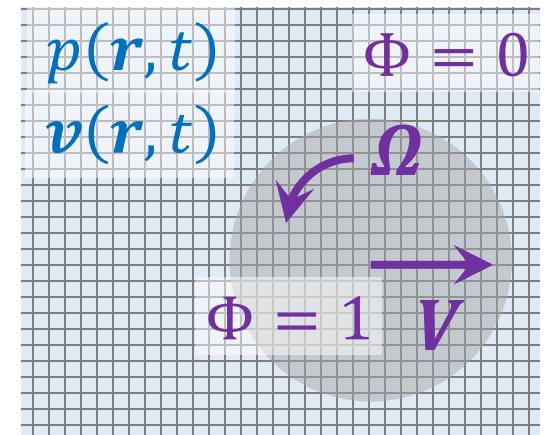
$$\nabla \cdot \mathbf{v} = 0$$

$$\boldsymbol{\sigma}_F = -pI + \eta[\nabla \mathbf{v} + (\nabla \mathbf{v})^\top]$$

Calculation on peculiar velocity: $\mathbf{v}' = \mathbf{v} - \dot{\gamma}(t)y\hat{x}$

Boundary conditions

x, z : Periodic, y : Lees-Edwards



Dynamic modulus

Input

$$\text{Shear strain } \gamma(t) = \gamma_0 \sin \omega t$$

$$\text{Shear rate } \dot{\gamma}(t) = \gamma_0 \omega \cos \omega t$$

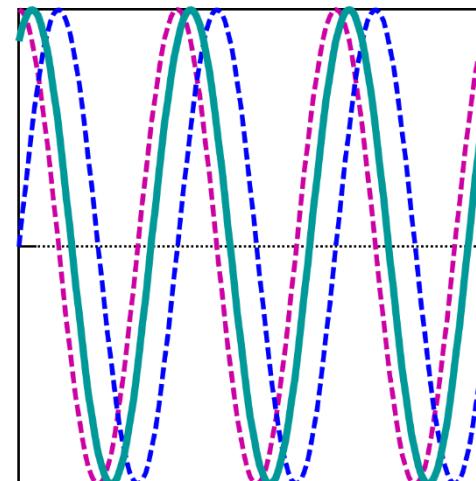
Output

$$\text{Stress } \sigma(t) = \sigma_0 \sin(\omega t + \delta)$$

$$= \gamma_0 (G' \sin \omega t + G'' \cos \omega t)$$

$$G' = \frac{\sigma_0}{\gamma_0} \cos \delta \quad G'' = \frac{\sigma_0}{\gamma_0} \sin \delta$$

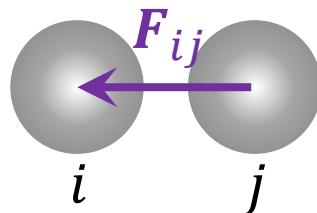
----- Shear strain
----- Shear rate
— Stress



Time

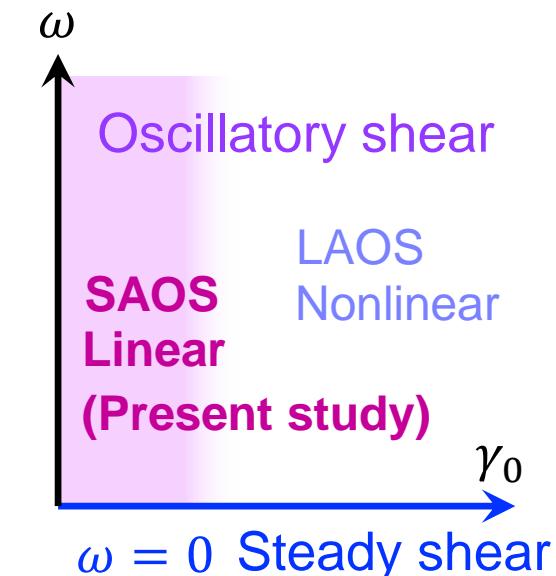
Stress

$$\sigma = \eta \dot{\gamma} + \frac{1}{V} \sum_i \int_{\partial P_i} (\boldsymbol{\sigma}_F \cdot \hat{\mathbf{n}})_x (y - y_i) dS - \frac{1}{V} \sum_{i < j} F_{ij}^x (y_i - y_j)$$



Dynamic modulus

$$G'(\omega) = \frac{\omega}{\pi \gamma_0} \int_0^{2\pi/\omega} \sigma(t) \sin \omega t dt \quad G''(\omega) = \frac{\omega}{\pi \gamma_0} \int_0^{2\pi/\omega} \sigma(t) \cos \omega t dt$$



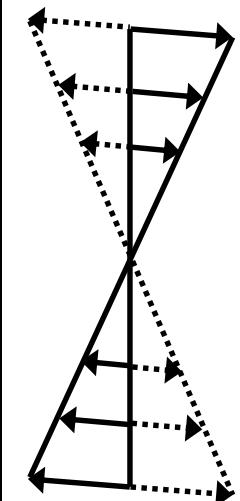
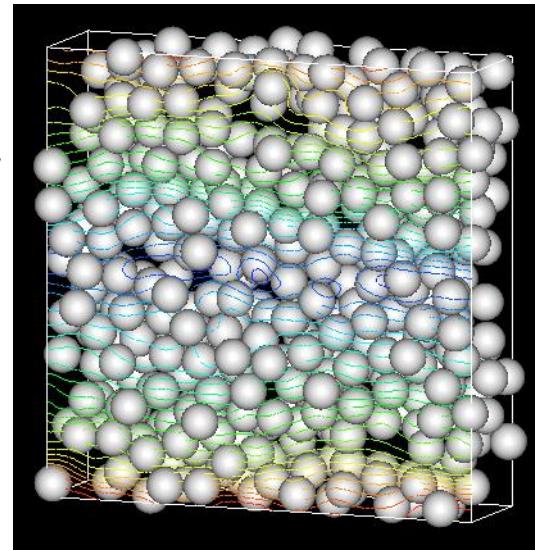
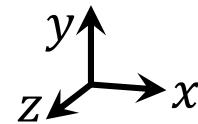
Simulation Conditions

Particles

- Diameter: $d = 100 \text{ nm}$
- Volume fraction: 0.5
- Zeta potential: 0 mV
- Adhesive force:

$$F^* = \frac{\rho}{\eta^2} F = 4.2 \times 10^{-4} - 4.2$$

$F^* = 4.2 \rightarrow \text{Hamaker constant } \sim 10^{-20} \text{ J}$



Fluid: Water

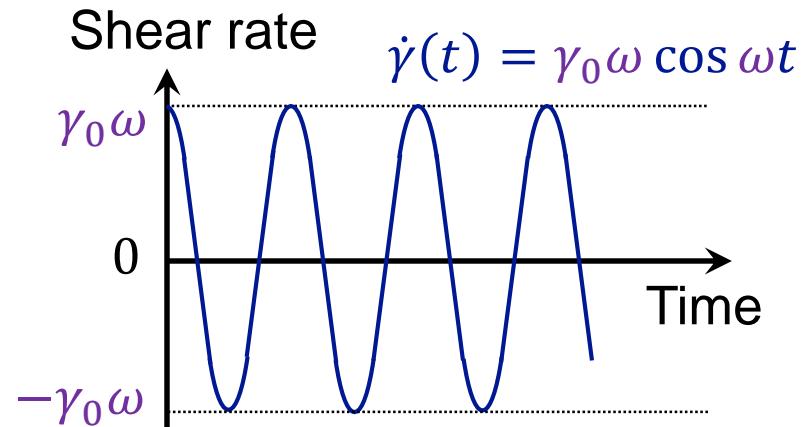
Fluid density: ρ
Viscosity: η

Shear flow

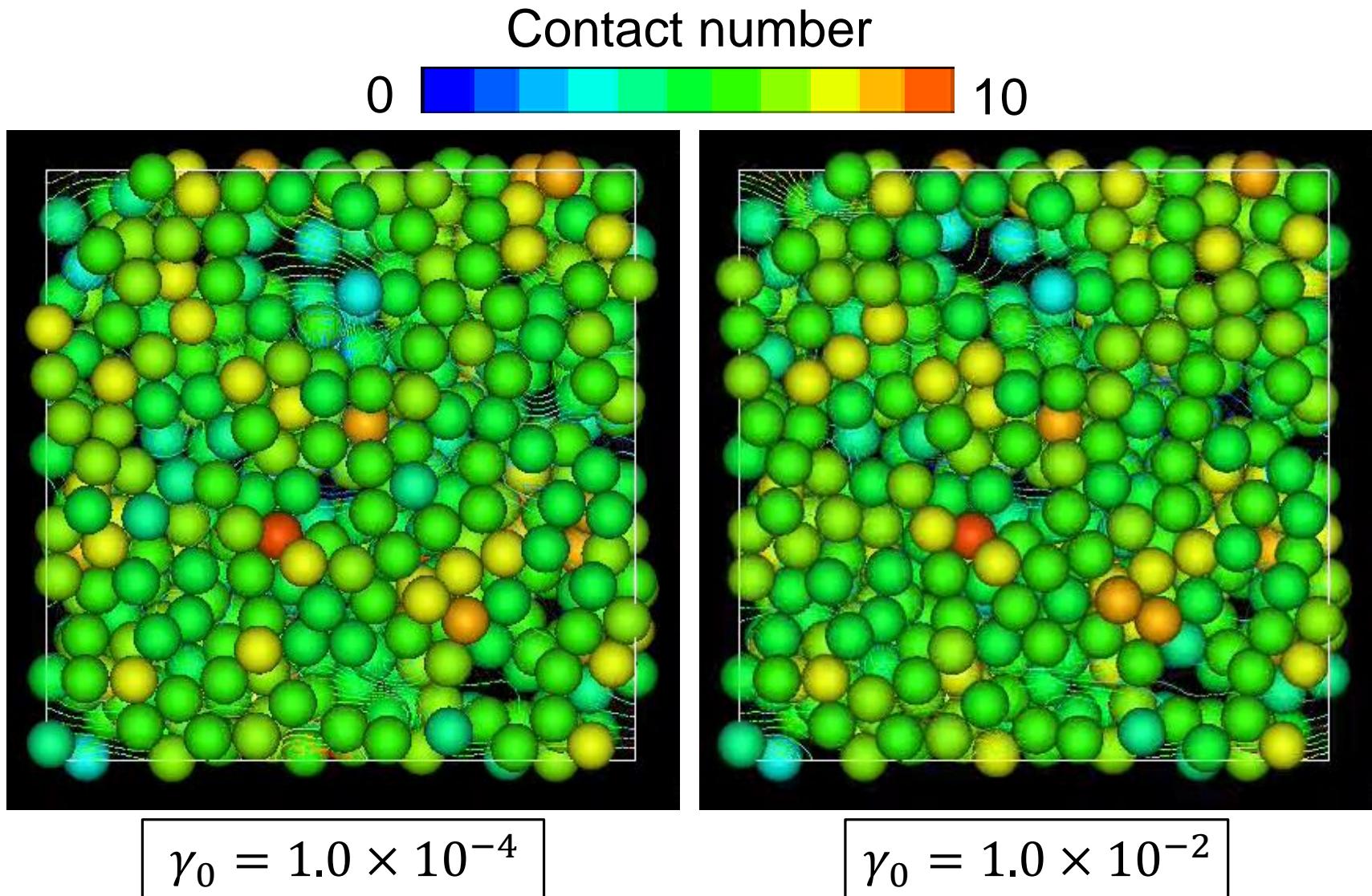
- Strain: $\gamma_0 = 3 \times 10^{-4} - 1 \times 10^{-1}$
- Frequency: $\omega \tau_{\text{vis}} = 3 \times 10^{-2} - 3$

$$\tau_{\text{vis}} = \frac{\rho d^2}{\eta} \quad \text{Timescale of momentum diffusion}$$

Domain size: $12d \times 12d \times 3d$



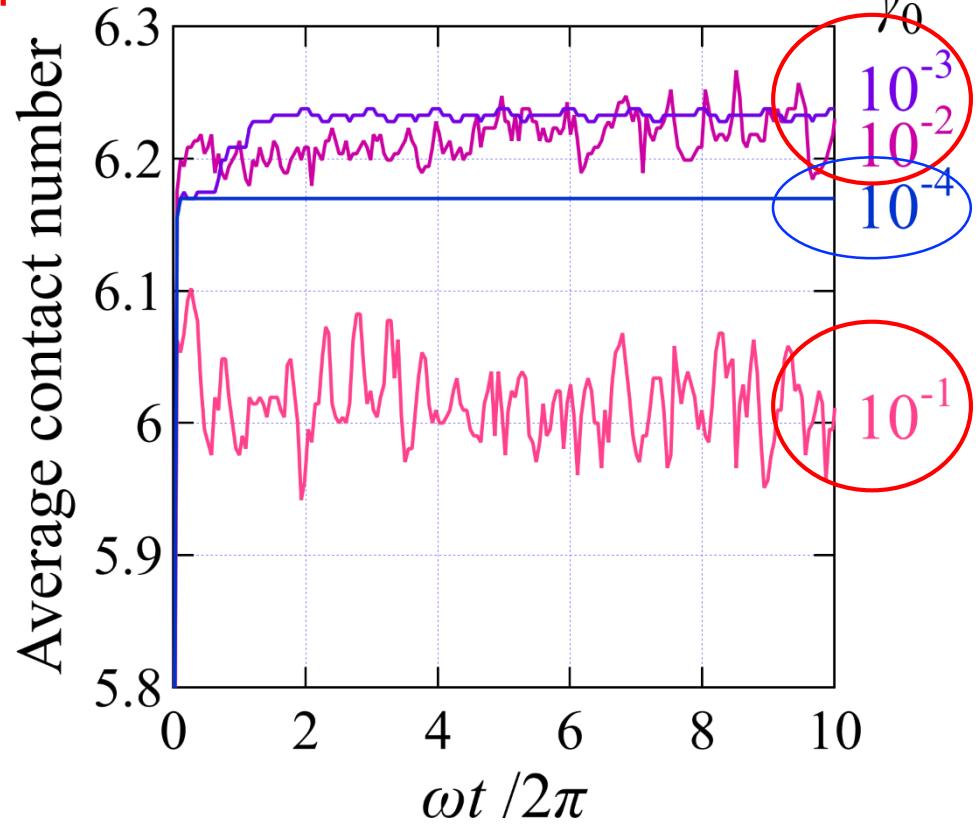
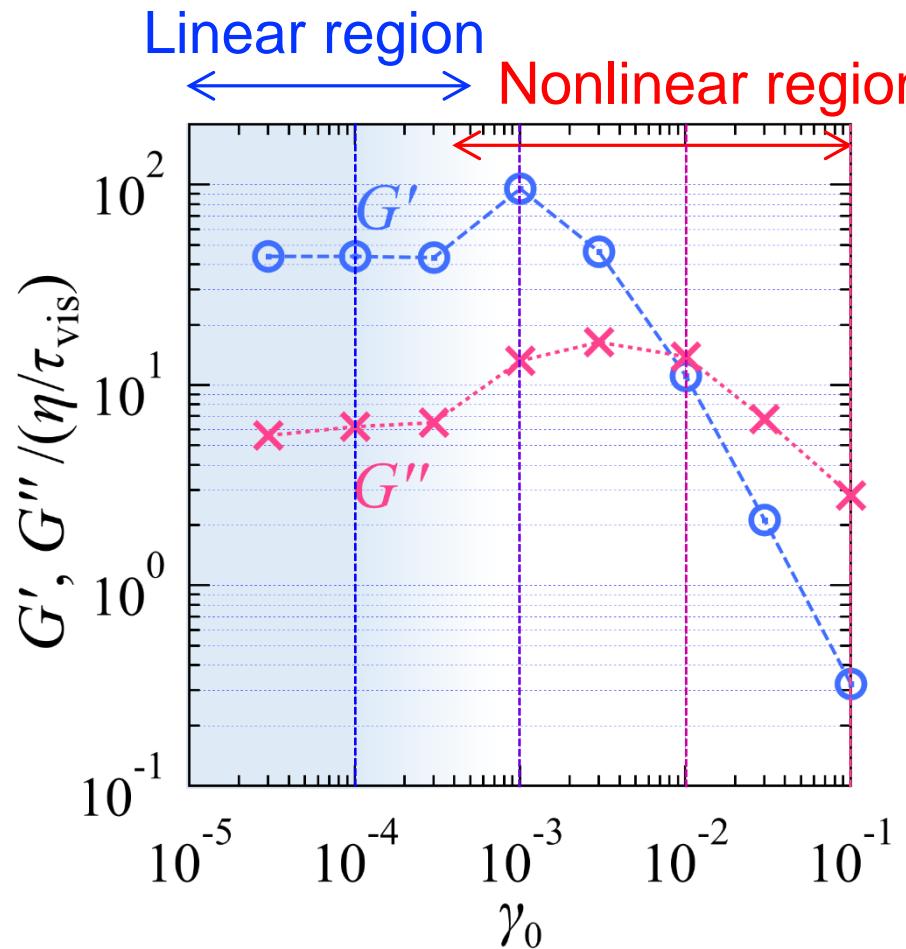
Structures in oscillatory shear flow



Strain dependence

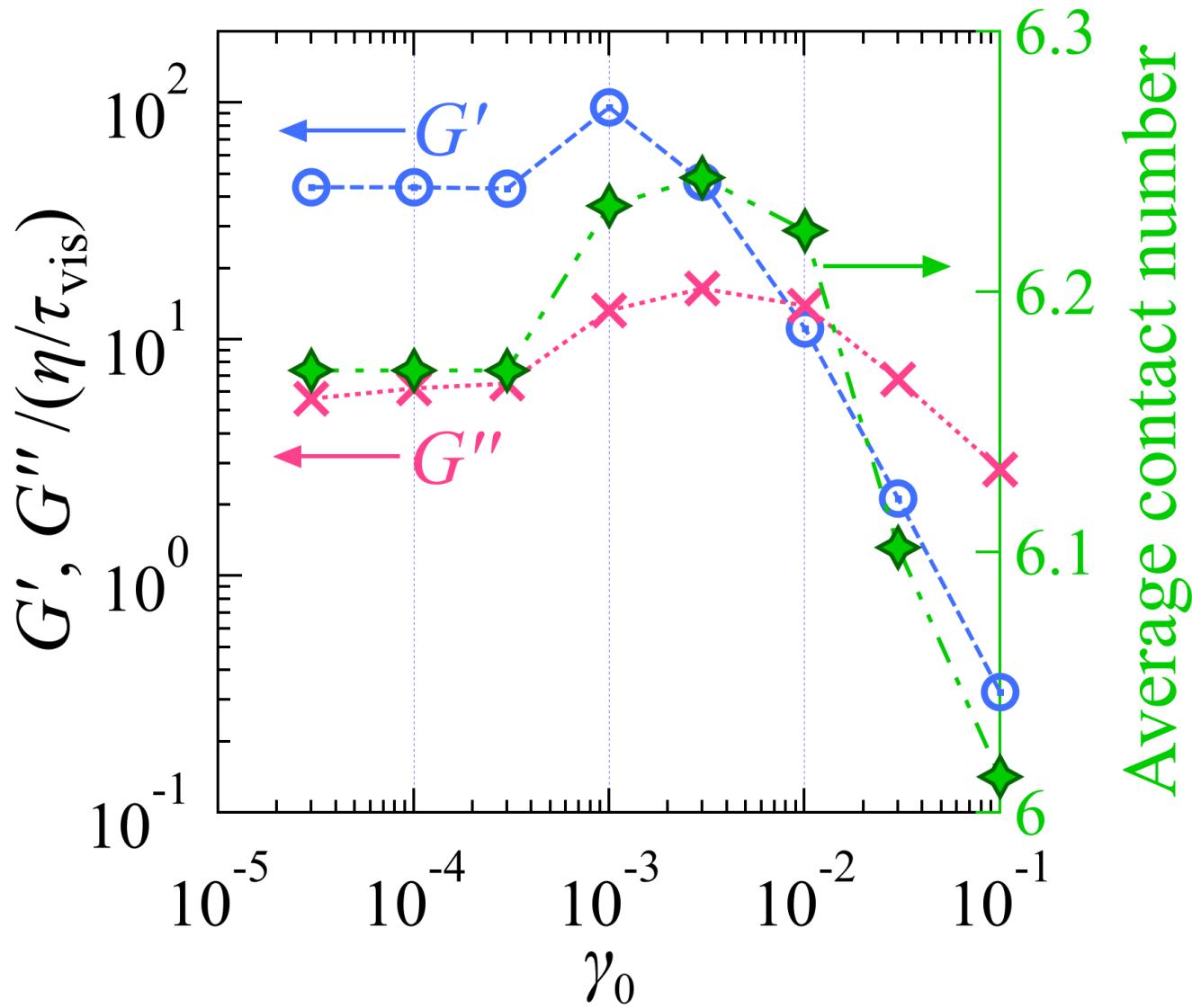
$$F^* = 4.2$$

$$\omega\tau_{\text{vis}} = 0.1$$



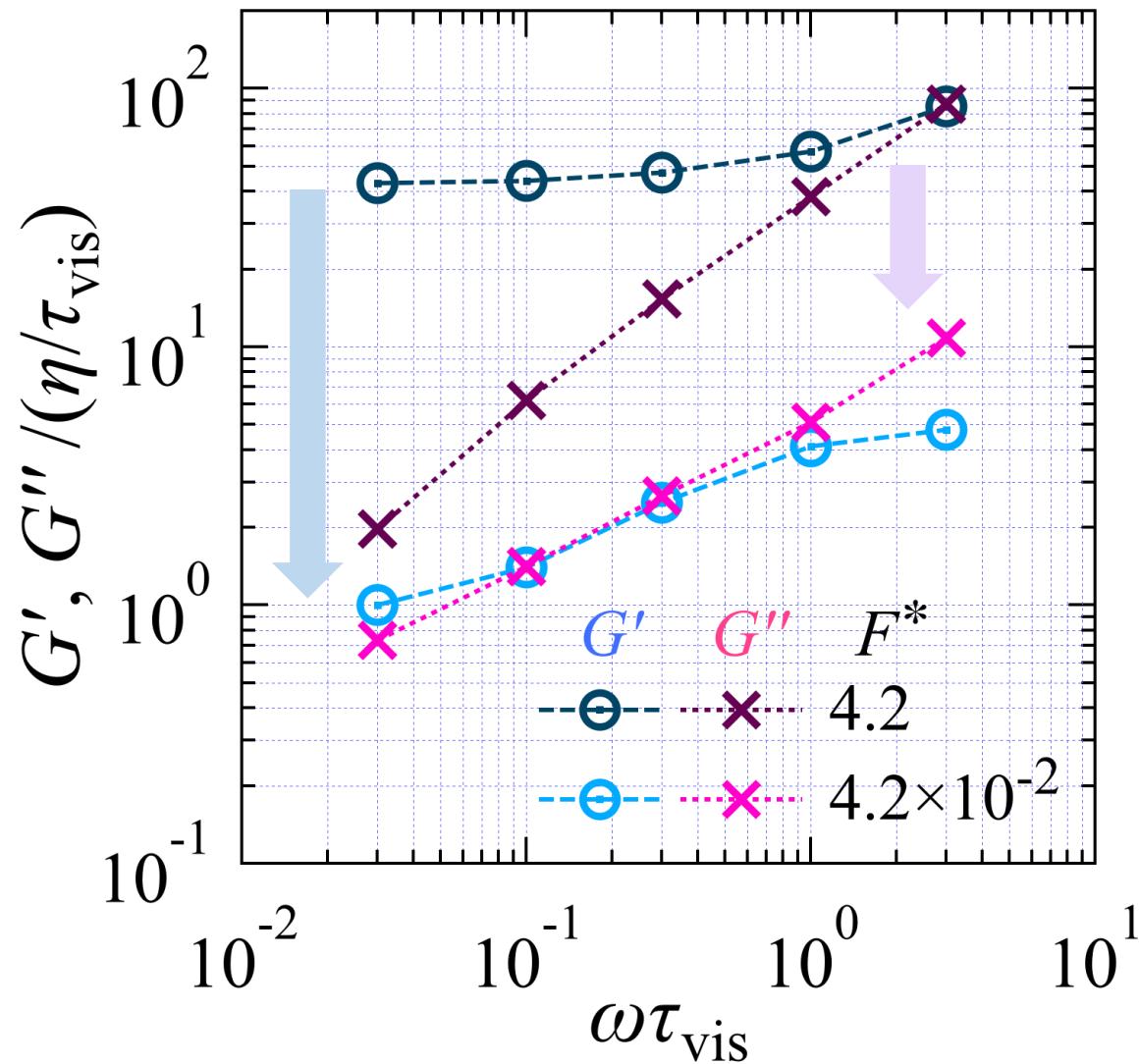
Linear region ← Little change in structure

Strain dependence



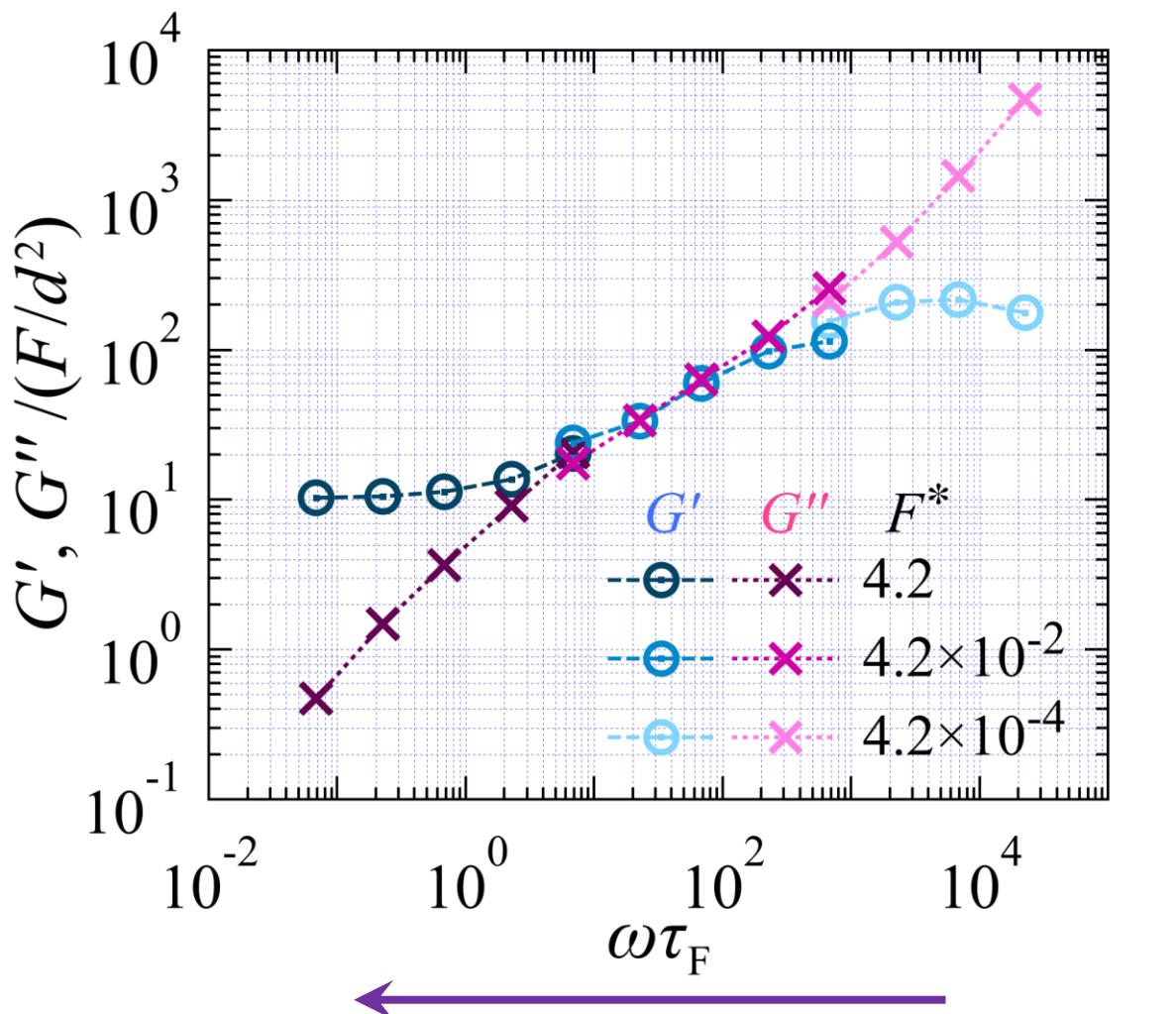
Effects of adhesive force

$$\gamma_0 = 10^{-4}$$



Frequency dependence

$$\gamma_0 = 10^{-4}$$



Larger adhesive force, Lower frequency

Adhesive force \sim Drag force

$$F \sim 3\pi\eta dU$$

Velocity of adhesion

$$U = \frac{F}{3\pi\eta d}$$

Relaxation time

$$\tau_F = \frac{d}{U} = \frac{3\pi\eta d^2}{F}$$

Summary

- Direct numerical simulation of viscoelastic behavior of concentrated colloidal suspensions
- Calculation of **dynamic modulus** in oscillatory shear flow
- Strain dependence reflects the structure change of particles
- Frequency dependence reflects relaxation of particle motion by adhesive force
- Increasing frequency corresponds to decreasing adhesive force